What is claimed is:

- 1. A plasma processing apparatus having a vacuum chamber for generating plenty of inductively coupled plasmas therein, comprising:
- a first very high frequency power source that supplies a very high frequency power having a frequency of 20 to 300MHz; and
- a plurality of antenna units being parallel-connected with each other and receiving the very high frequency power from the first very high frequency power source;

an antenna being comprised of the plurality of antenna unit;

wherein the vacuum chamber has a reaction space where the inductively coupled plasmas are generated by the plurality of antenna units.

- 2. An apparatus according to claim 1, wherein one of the antenna units has at least one variable load that is connected in series.
- 3. An apparatus according to claim 2, wherein the antenna units having at least one variable load is located in an outer part of the antenna.
- 4. An apparatus according to claim 3, wherein the variable load is a variable capacitor.
- 5. An apparatus according to claim 1, further comprising an impedance matching box that is connected to the very high frequency power source and the antenna.

- 6. An apparatus according to claim 5, wherein the parallel-connected antenna units maintain a resonance state therebetwee.
- 7. An apparatus according to claim 6, further comprising a chuck in the vacuum chamber for mounting a substrate thereon.
- 8. An apparatus according to claim 7, further comprising a second very high frequency power source that supplies a very high frequency power having a frequency of 20 MHz to 300 MHz to the chuck.
 - 9. An RF power supplying apparatus, comprising:

a very high frequency power source supplying a very high frequency power having a frequency of 20 MHz to 300 MHz;

an impedance matching box connected to the very high frequency power source; a plurality of antenna units connected in parallel with each other; and an antenna being comprised of the plurality of antenna units; and wherein each antenna unit has at least one variable capacitor and a coil antenna.